support and a UV-sensitive layer, wherein the adhesive layer is laminated to the UV-sensitive layer.

(b) image-wise exposing the image recording layer to form a mask;

(c) flood exposing the UV-sensitive material through the mask;

(d) developing the UV-sensitive material;

wherein the peelable support is removed either before step (b) , (c) or (d) and wherein steps (a) to (d) are performed within a period of less than 2 months.

21. Method according to claim 20 wherein the UV-sensitive material further comprises an additional layer on top of the UV-sensitive layer and wherein the adhesive is laminated on top of the additional layer.

22. Method according to claim 20 wherein the image recording layer is a laser ablatable layer comprising a heat combustible polymeric binder and a light absorbing compound.

23. Method according to claim 20 wherein the image recording layer is a thin metallic layer.

24. Method according to claim 20 wherein the image recording layer is an ink jet receiving layer.

25. Method according to claim 20 wherein the image recording layer is a thermographic recording layer.

26. Method according to claim 20 wherein the image recording layer is a photothermographic recording layer.

27. Method according to claim 20 wherein the first peelable support is a plastic film coated with a release agent on the side facing the image recording layer.

28. Method according to claim 20 wherein said adhesive layer is a thermosensitive adhesive layer.

29. Method according to claim 20 wherein said adhesive layer is a pressure-

sensitive adhesive layer.

30. Method according to claim 29 wherein said pressure-sensitive adhesive layer is covered by a second peelable support which is removed before step (a).

31. Method according to claim 30 wherein the second peelable support is a plastic film coated with a release agent on the side facing the pressure-sensitive adhesive layer.

32. Method according to claim 27 wherein the release agent is a silicone.

33. Method according to claim 20 wherein said UV-sensitive material is a photoresist material.

34. Method according to claim 20 wherein said UV-sensitive material is a lithographic printing plate precursor.

35. Method according to claim 20 wherein said UV-sensitive material is a flexographic printing plate precursor.

36. Method according to claim 20 wherein the mask is removed by the developing step (d).

37. Method according to claim 20 wherein the mask is removed by an additional developing step between step (c) and step (d).

38. Method according to claim 20 wherein the mask is removed by peel-off before developing step (d).